

IN THE CLAIMS

The status of the claims is reproduced below.

1. (Currently Amended): A method for cleaning a resist residue on a microstructure comprising fluidizing a cleaning agent composition consisting essentially of carbon dioxide and a cleaning component under a pressure of 5 Mpa or more, and bringing the cleaning agent composition into contact with a resist residue on a microstructure, wherein hydrogen fluoride is used as the cleaning component, wherein the hydrogen fluoride concentration in the cleaning agent composition is 0.0001 to 0.05% by mass,

wherein the water content in the cleaning agent composition is controlled to 0.0001 to 0.5% by mass.

Claim 2: (Canceled).

3. (Original): The method according to Claim 1, wherein the cleaning agent composition is prepared by mixing hydrofluoric acid and high-pressure carbon dioxide.

Claims 4-6: (Canceled).

7. (Previously Presented): A method for cleaning a resist residue on a microstructure comprising:

fluidizing a cleaning agent composition consisting essentially of carbon dioxide, a cleaning component and 1% by mass or more of an alcohol under a pressure of 5 Mpa or more, and

bringing the cleaning agent composition into contact with a resist residue on a microstructure, wherein hydrogen fluoride is used as the cleaning component, wherein the hydrogen fluoride concentration in the cleaning agent composition is 0.0001 to 0.05% by mass,

wherein the water content in the cleaning agent composition is controlled to 0.0001 to 0.5% by mass.

8. (Previously Presented): The method according to Claim 7, wherein the cleaning agent composition is prepared by mixing hydrofluoric acid and high-pressure carbon dioxide.

Claims 9-10: (Canceled).

SUPPORT FOR THE AMENDMENTS

Claims 1 and 7 have been amended to include the subject matter of Claims 4 and 9, respectively. Claims 4 and 9 have been canceled along with Claims 6 and 10. Accordingly, no new matter is believed to have been added to the present application by the amendments submitted above.